

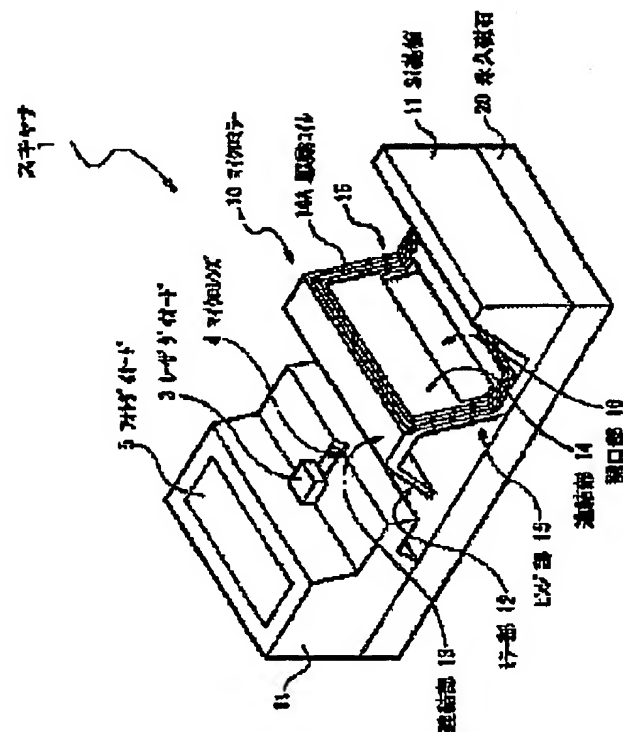
MICROMIRROR AND METHOD OF MANUFACTURING FOR THE SAME

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Abstract of JP2002244053

PROBLEM TO BE SOLVED: To provide a micromirror which can be manufactured by a simple process step and can be displaced to a wide angle and a method of manufacturing for the same. **SOLUTION:** The (111) face formed by subjecting a silicon (100) substrate 11 to anisotropic etching is used as a mirror section 12 and a connecting section 14. The connecting section 14 is provided with a driving coil 14A. A permanent magnet 20 is installed to the underside of the silicon substrate 11 and electric current is passed to the driving coil 14A in the magnetic field of the permanent magnet 20, by which a Lorentz's force is generated and a hinge section 15 is moved back and forth in a direction approximately parallel to the (100) face of the silicon substrate 11. As this hinge section 15 is driven, the mirror section 12 is displaced to wide angles.



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